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FIG. 1A

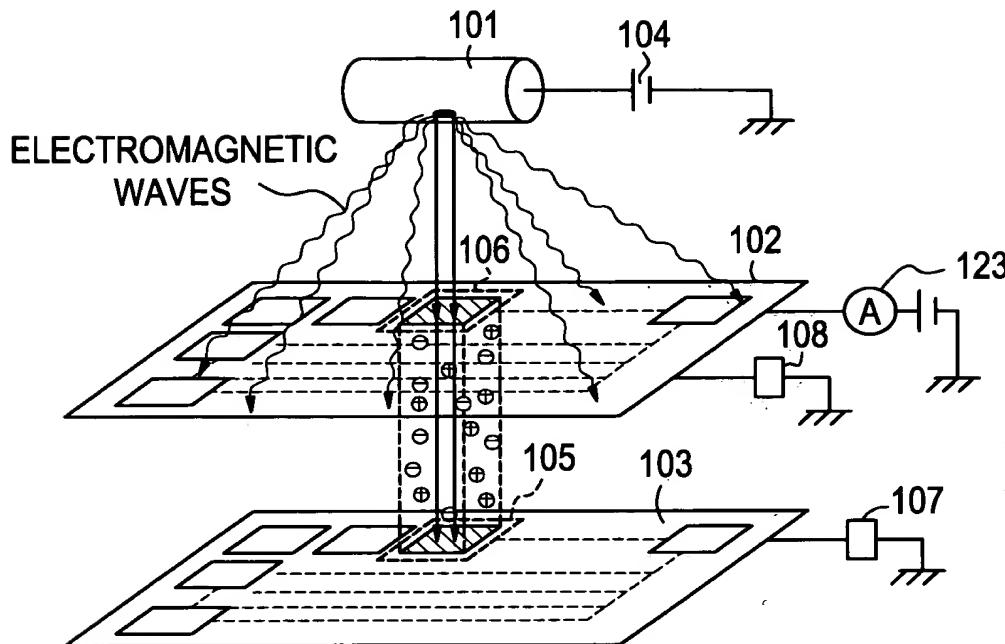


FIG. 1B

ENLARGED DIAGRAM OF 105

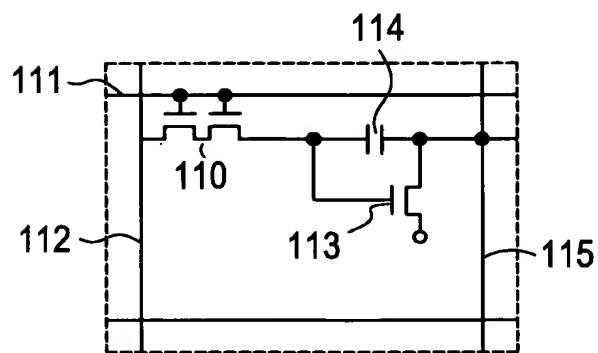
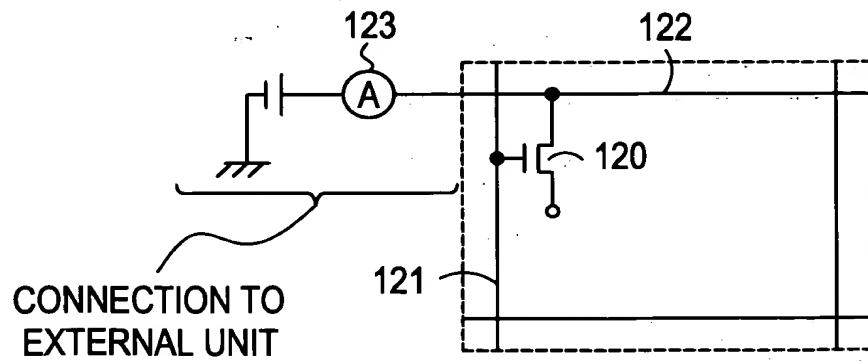


FIG. 1C

ENLARGED DIAGRAM OF 106





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FIG. 2A

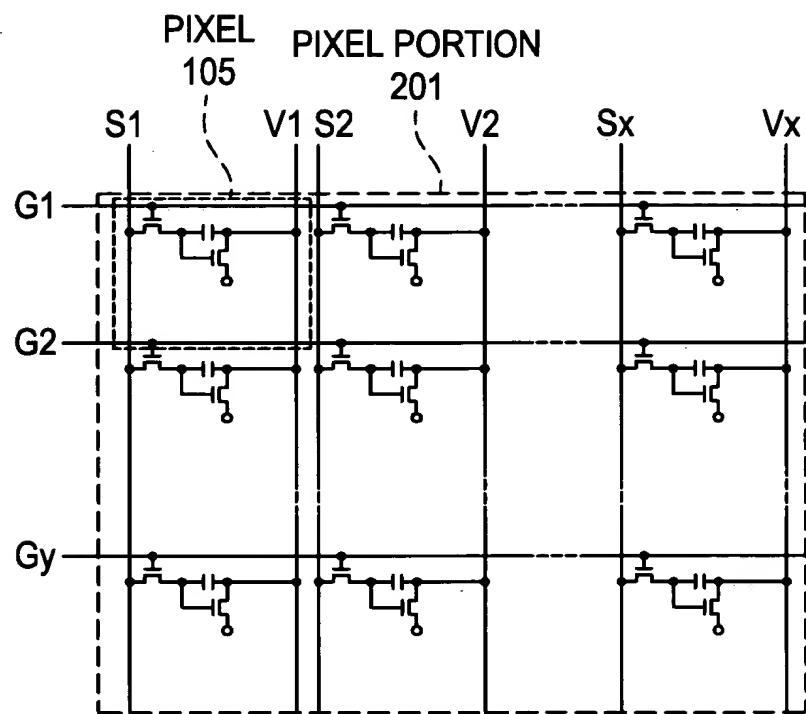
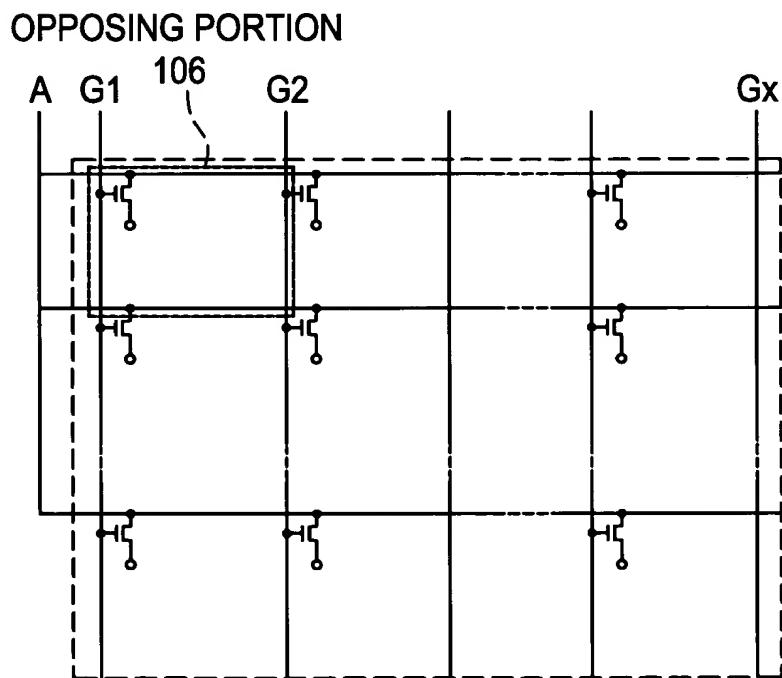


FIG. 2B





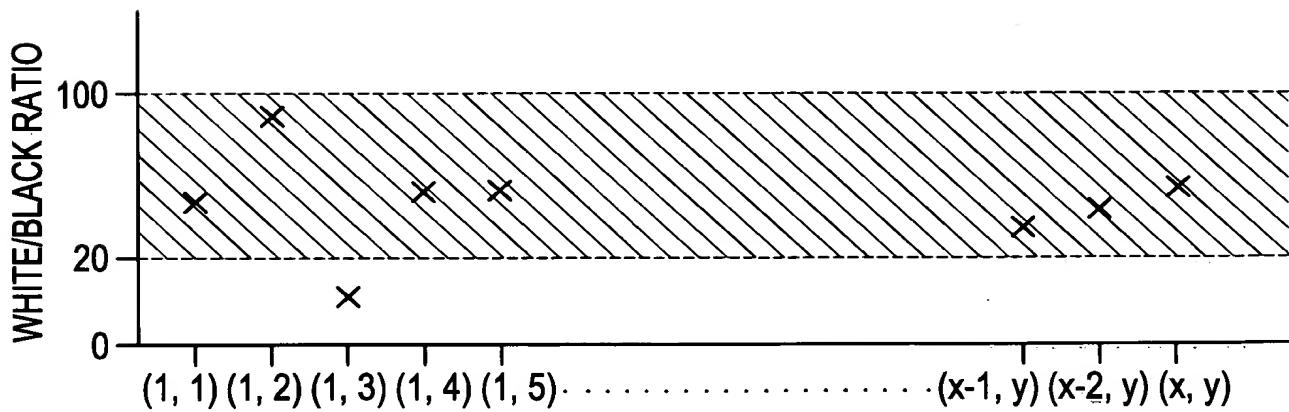
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FIG. 3A

(1, 1)	(2, 1)	(3, 1)	(4, 1)		(x-1, 1)	(x, 1)
(1, 2)	(2, 2)	(3, 2)	(4, 2)		(x-1, 2)	(x, 2)
(1, 3)	(2, 3)	(3, 3)	(4, 3)		(x-1, 3)	(x, 3)
(1, 4)	(2, 4)	(3, 4)	(4, 4)		(x-1, 4)	(x, 4)
(1, y-1)	(2, y-1)	(3, y-1)	(4, y-1)		(x-1, y-1)	(x, y-1)
(1, y)	(2, y)	(3, y)	(4, y)		(x-1, y)	(x, y)

FIG. 3B





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FIG. 4A

FORMATION OF ISLAND SEMICONDUCTOR LAYER, GATE-INSULATING FILM,
AND FIRST AND SECOND CONDUCTING FILMS FOR GATE ELECTRODES

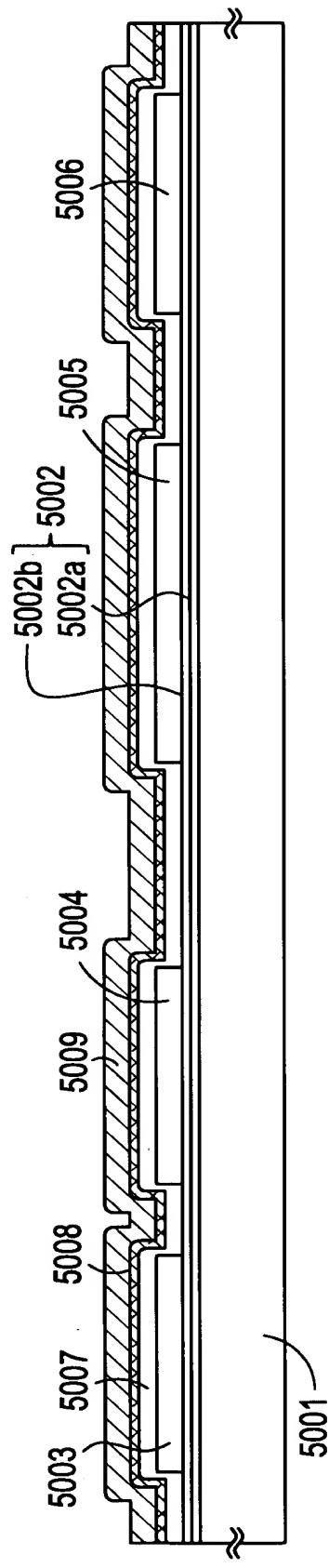
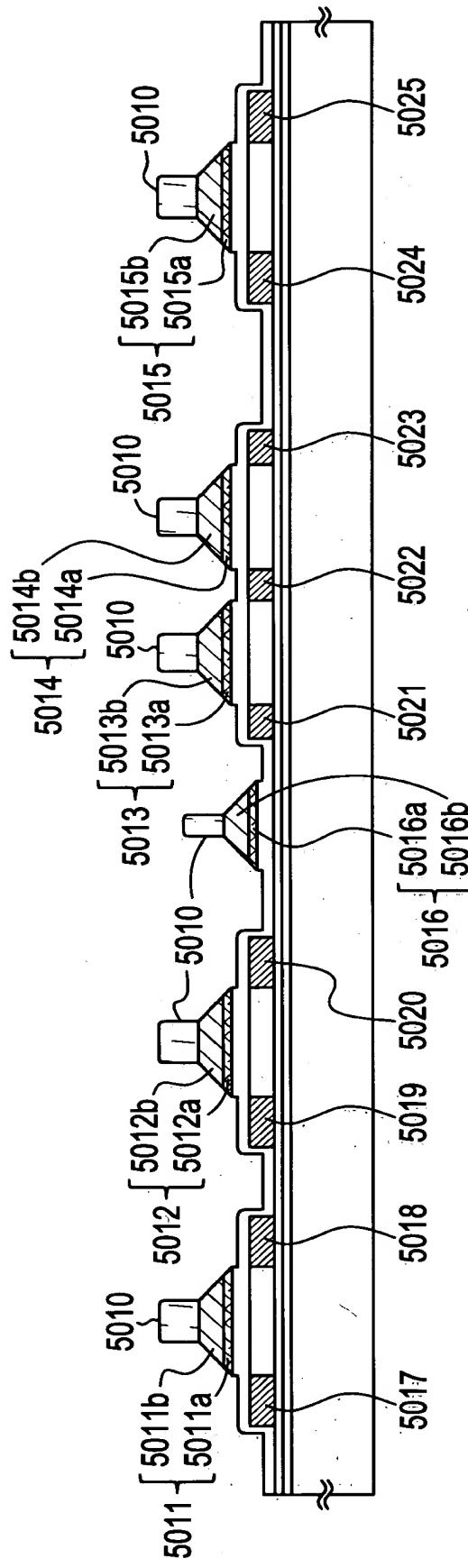


FIG. 4B

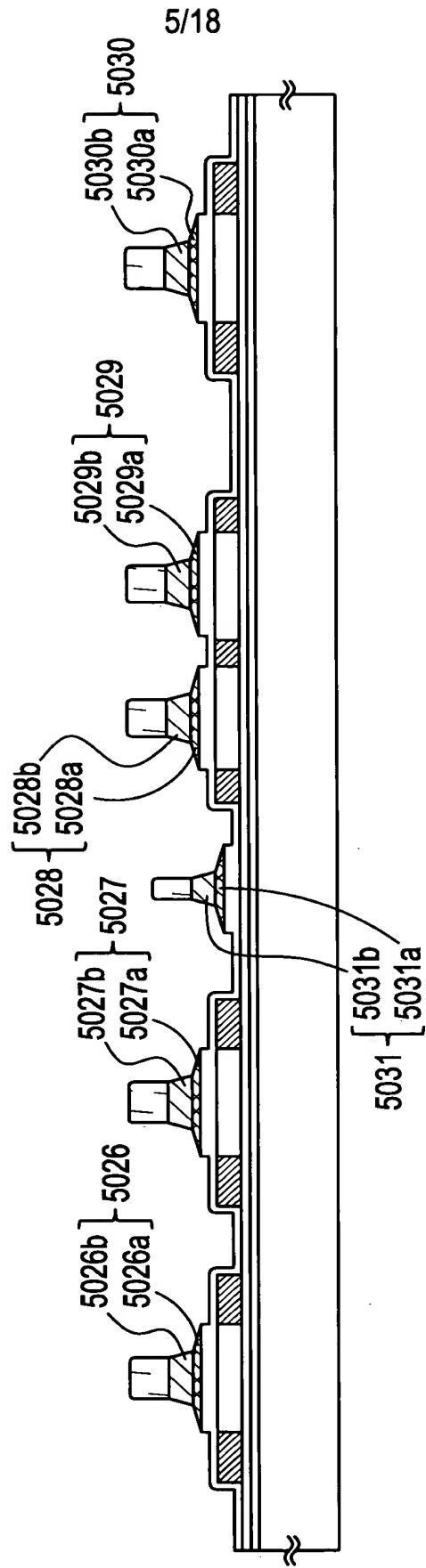
FIRST ETCHING AND FIRST DOPING





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FIG. 4C
SECOND ETCHING



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FIG. 5A
SECOND DOPING

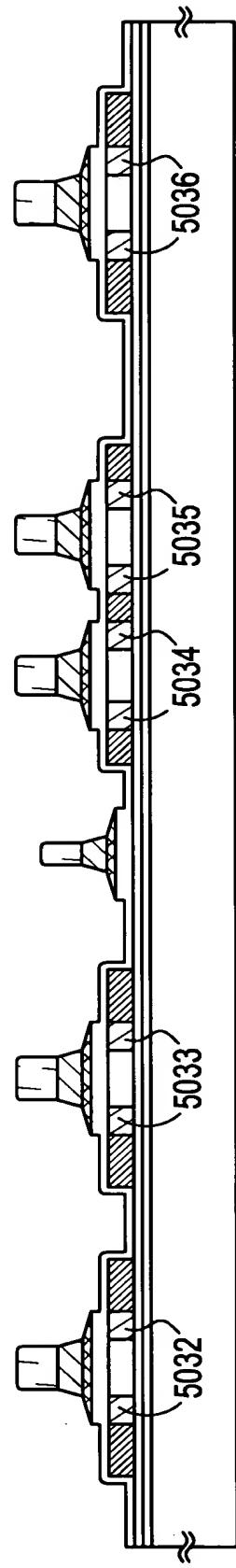
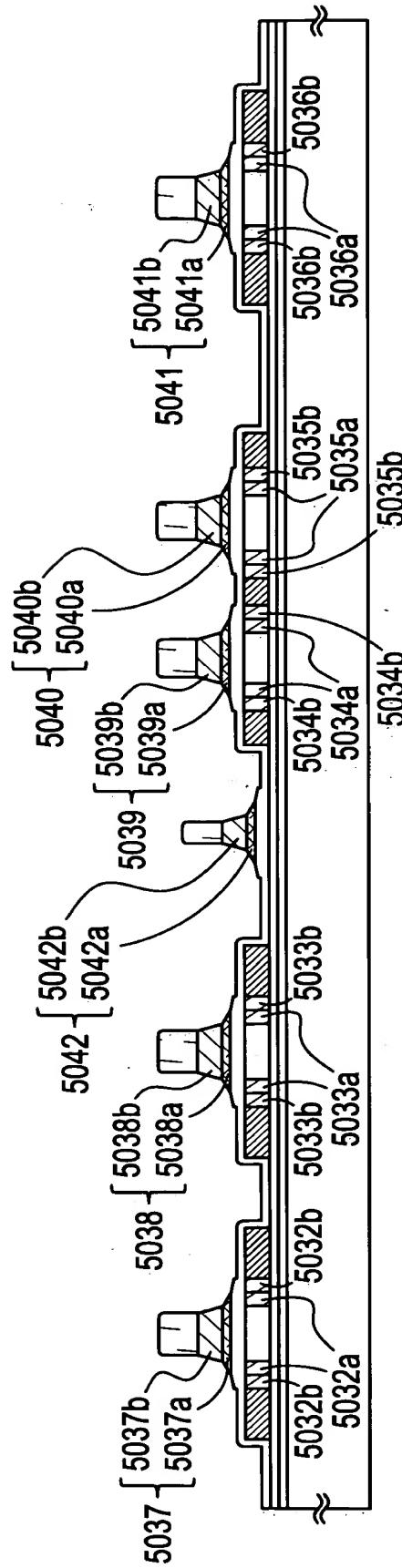


FIG. 5B
THIRD ETCHING



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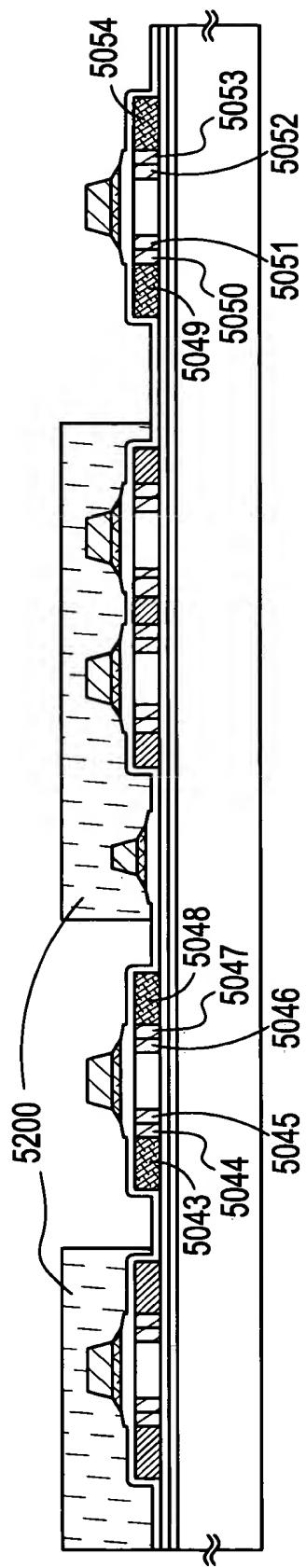


FIG. 5C
THIRD DOPING

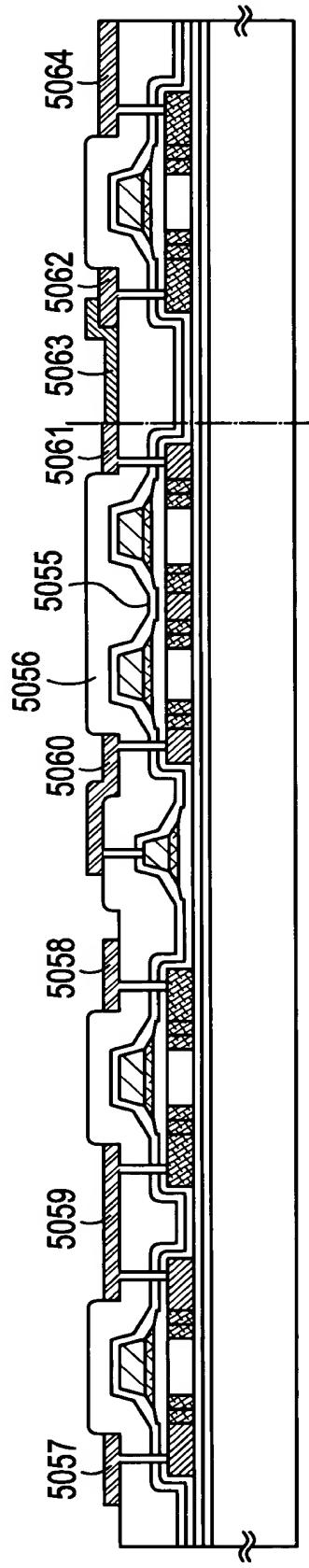


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FIG. 6A

FORMATION OF THE FIRST AND SECOND INTERLAYER-INSULATING FILMS, WIRINGS AND PIXEL ELECTRODES

**FIG. 6B**

FORMATION OF THE THIRD INTERLAYER-INSULATING FILM, EL LAYER, CATHODES AND PASSIVATION FILM

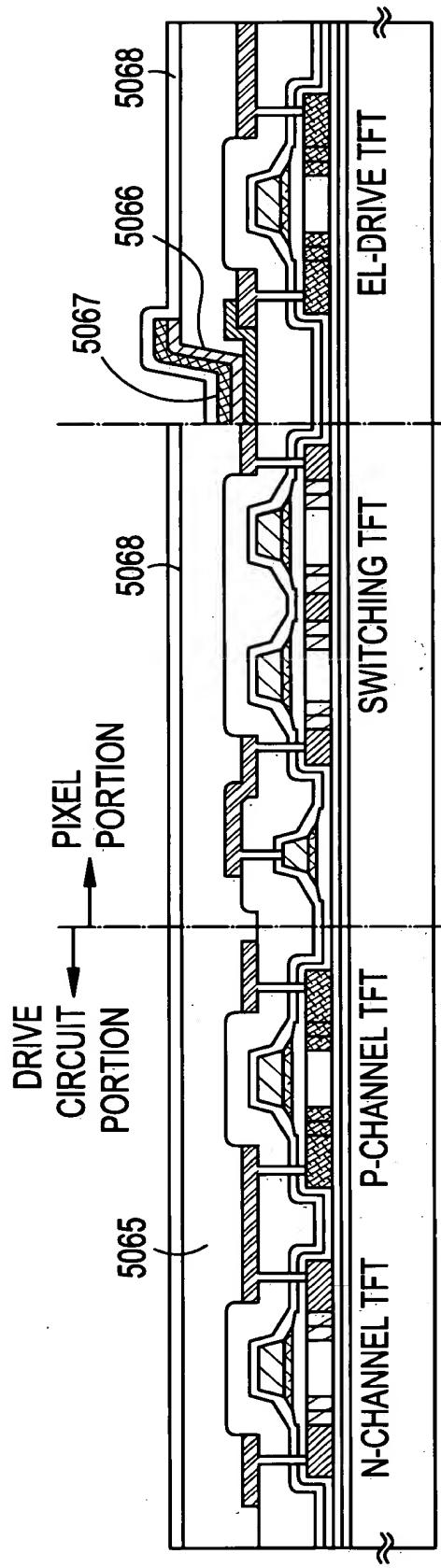


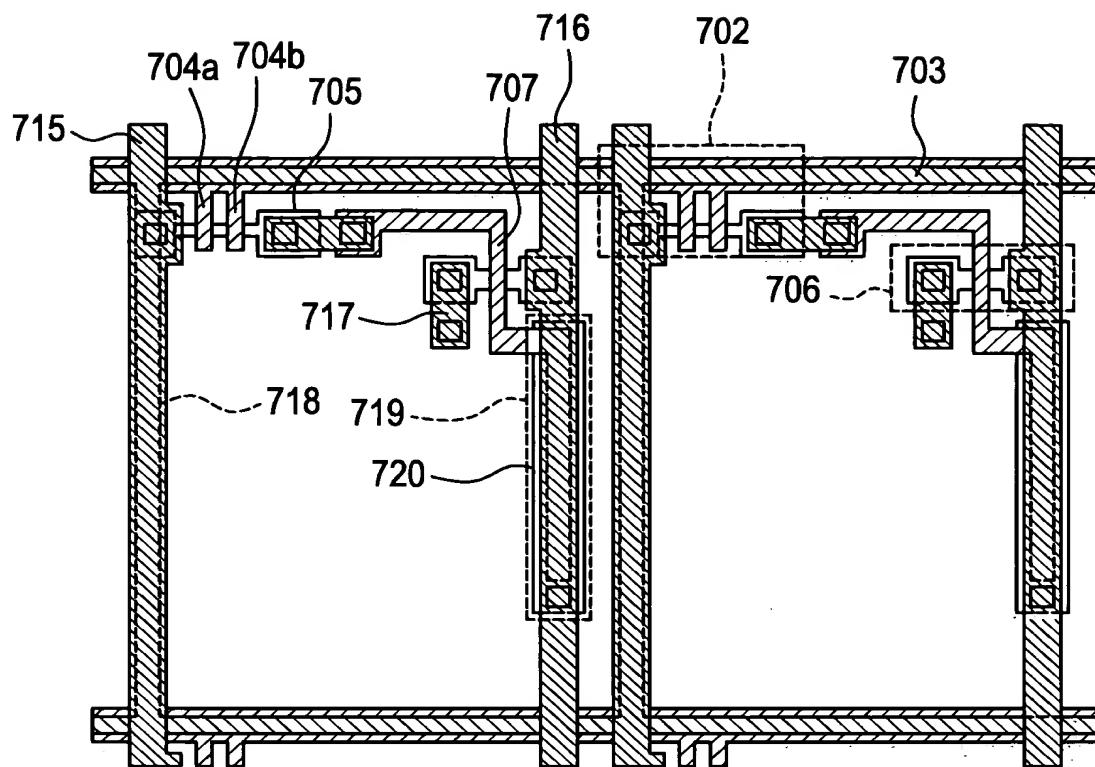
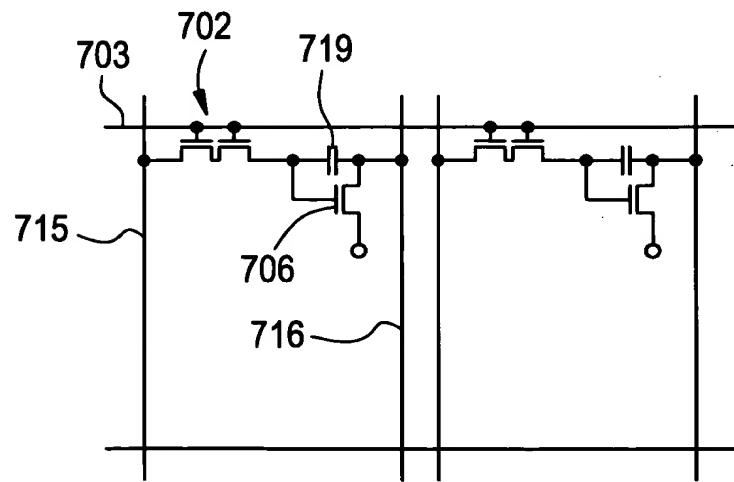
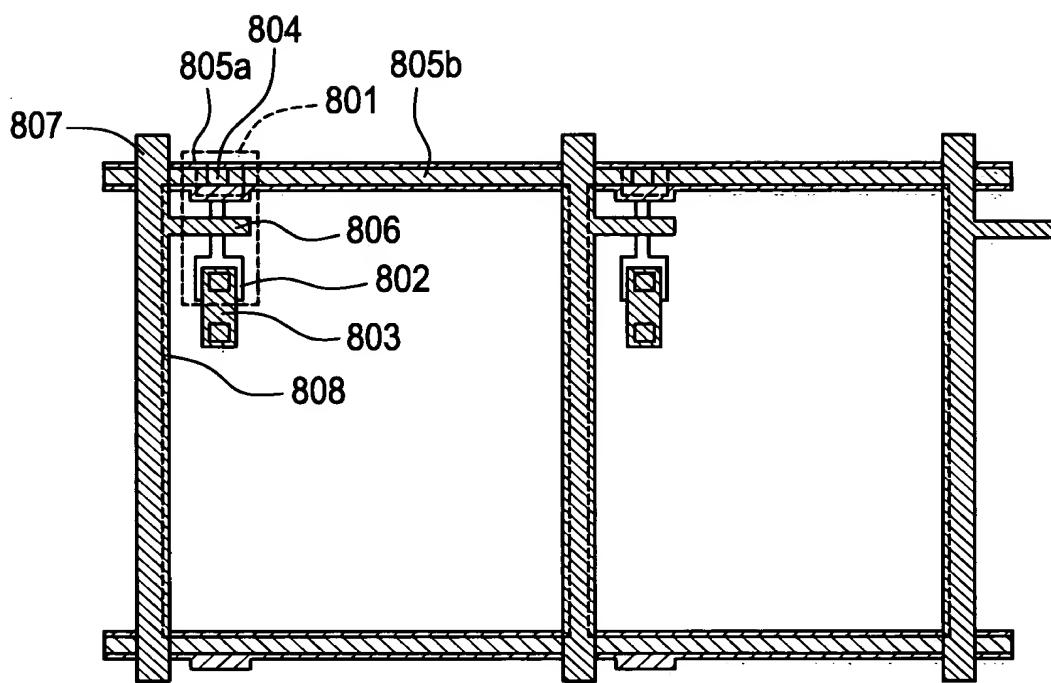
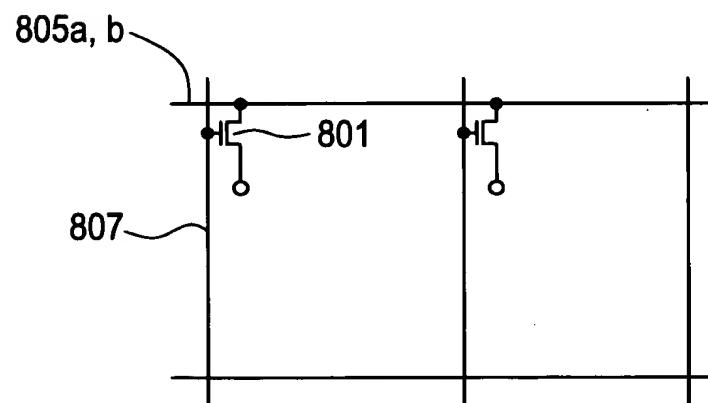
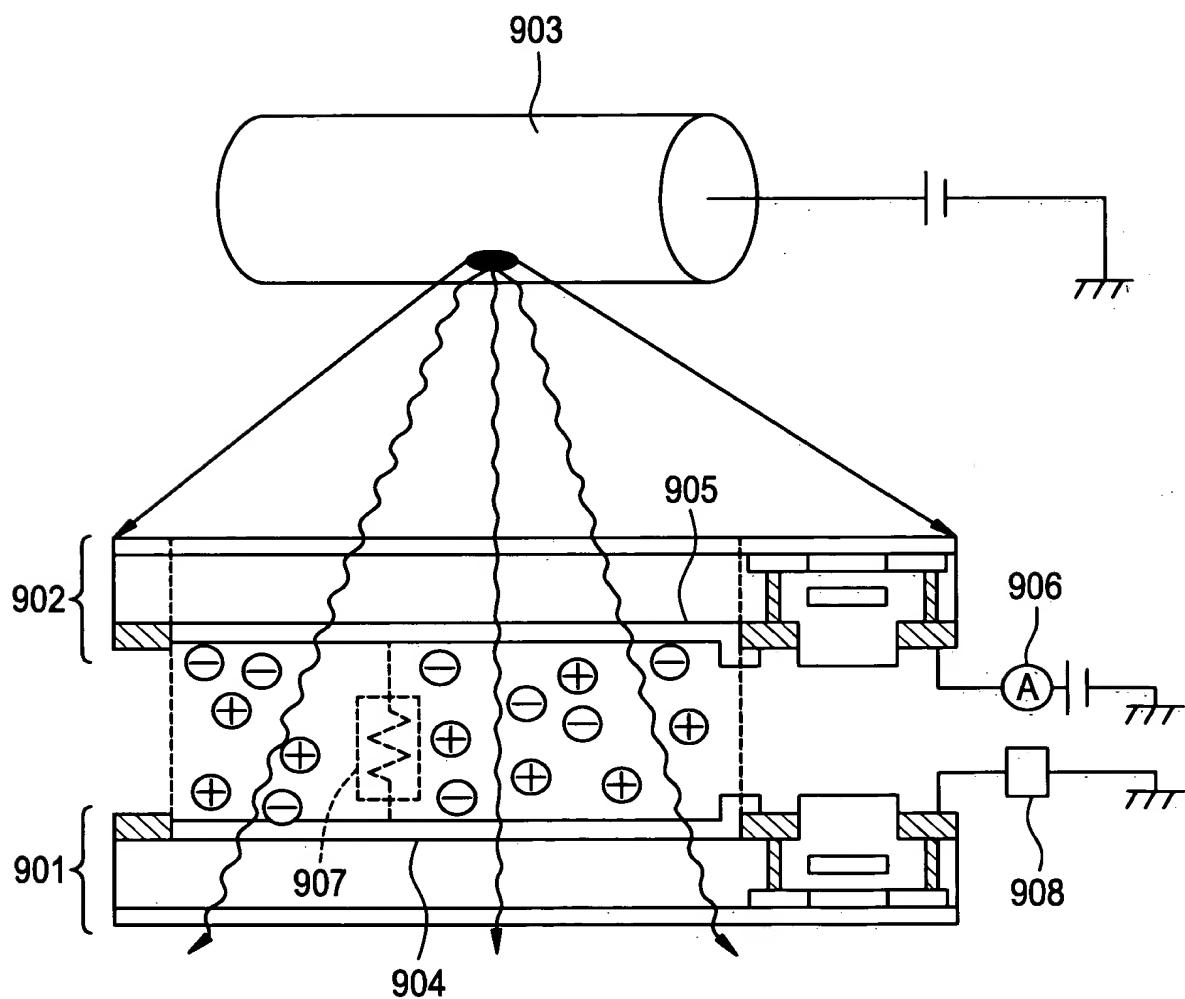
FIG. 7A**FIG. 7B**

FIG. 8A**FIG. 8B**



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FIG. 9



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FIG. 10

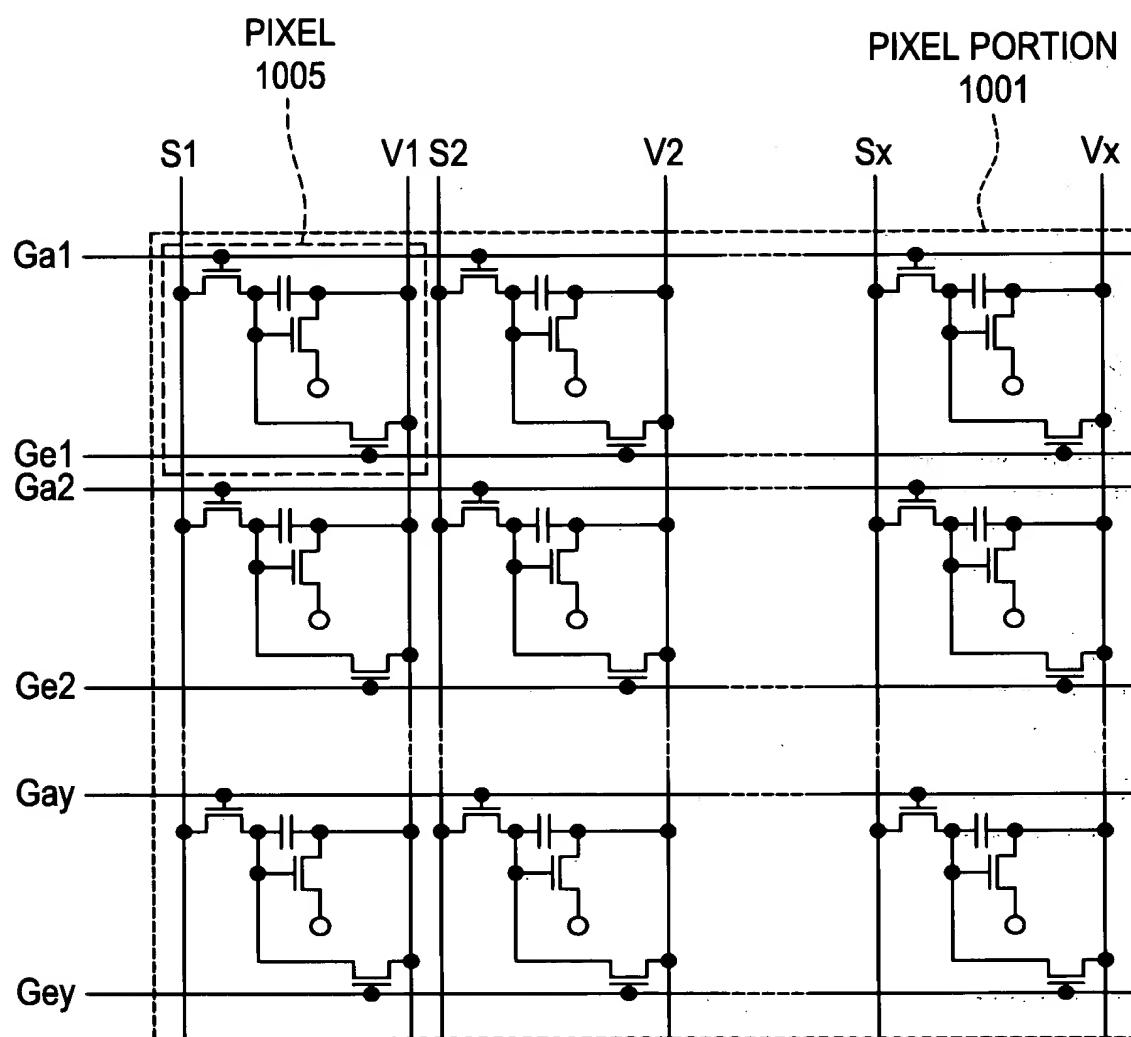


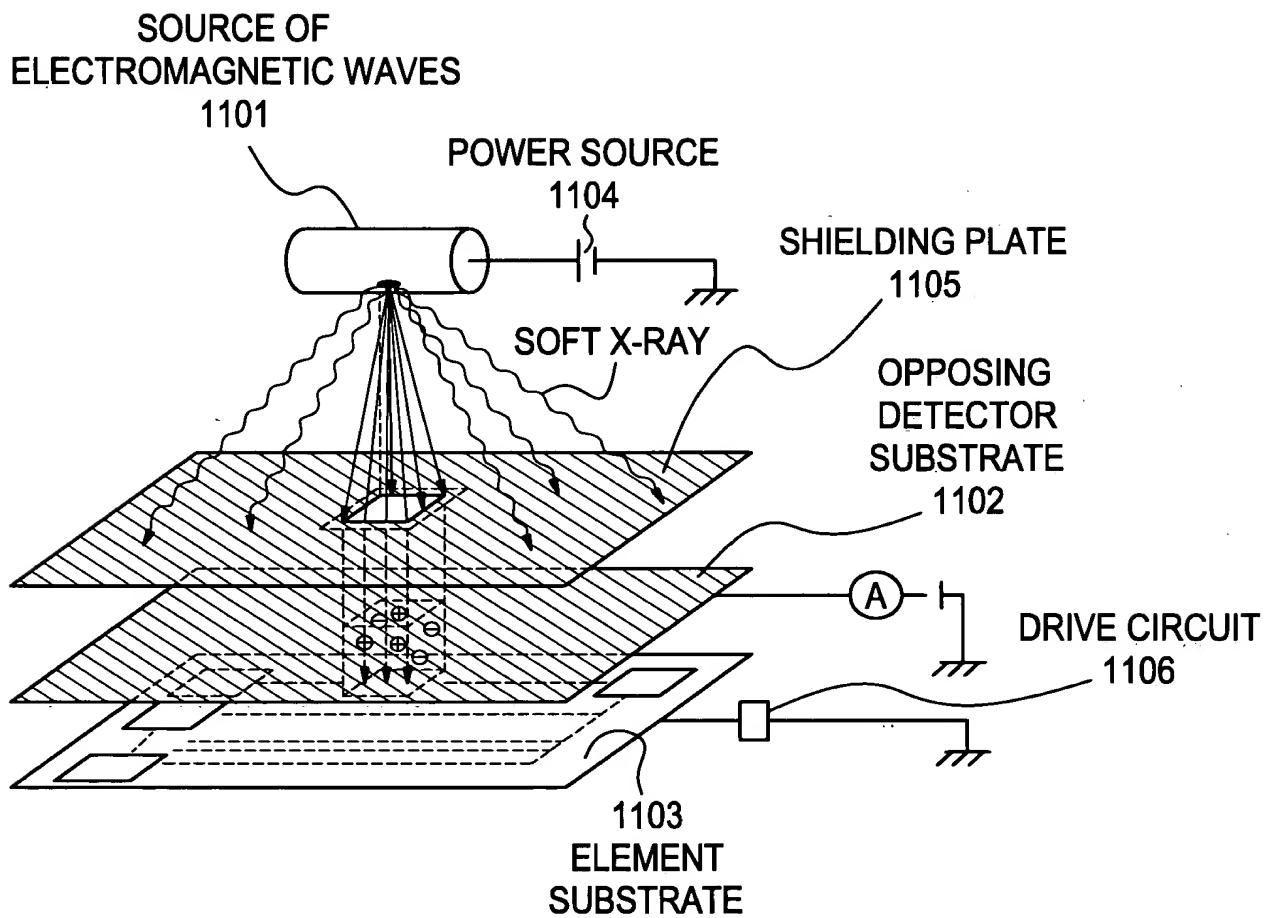
FIG. 11

FIG. 12

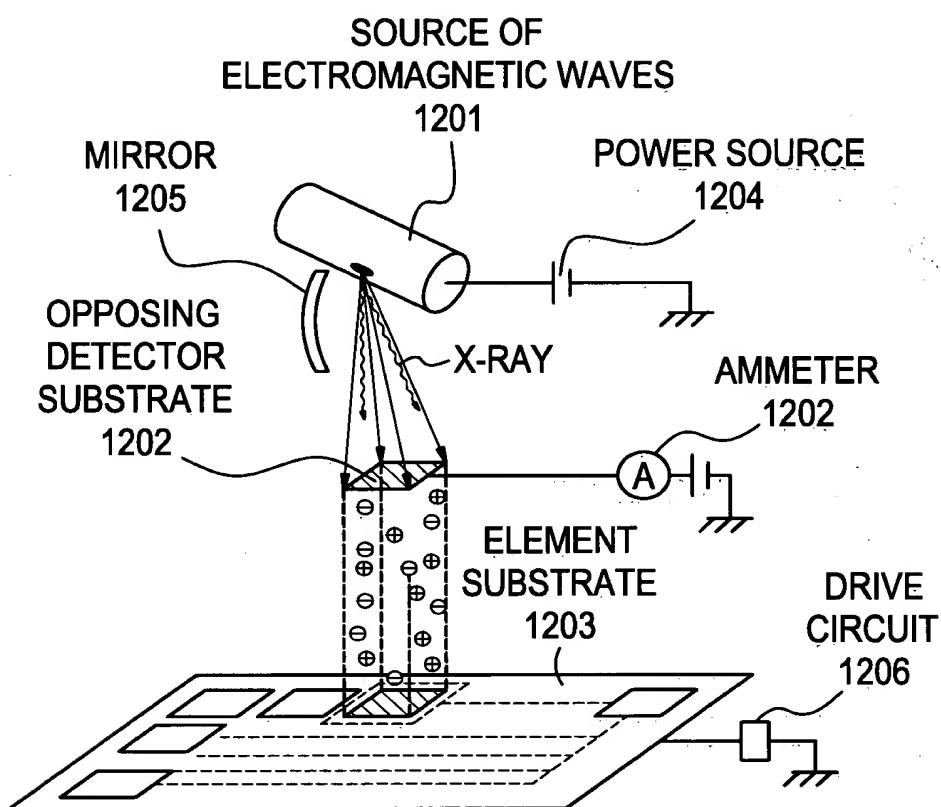


FIG. 13A

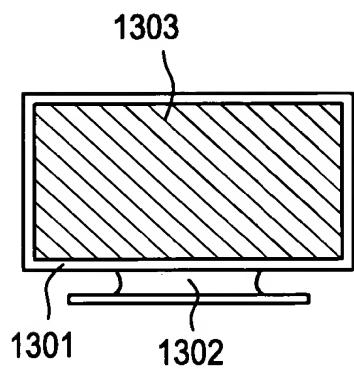


FIG. 13B

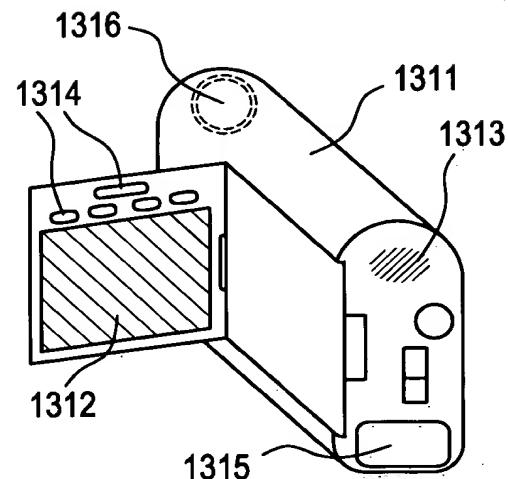


FIG. 13C

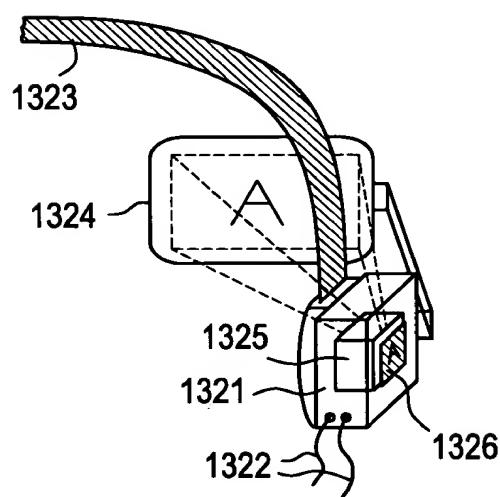


FIG. 13D

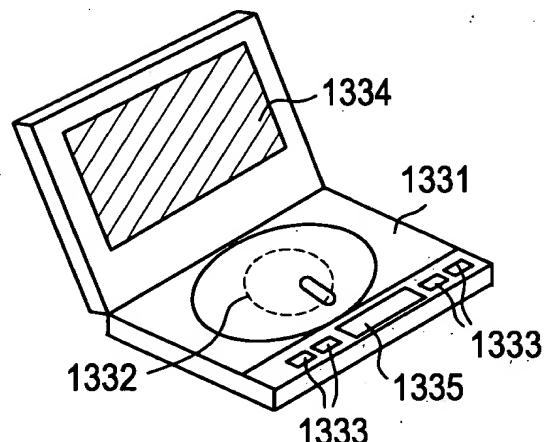


FIG. 13E

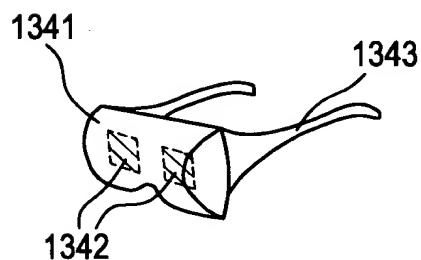
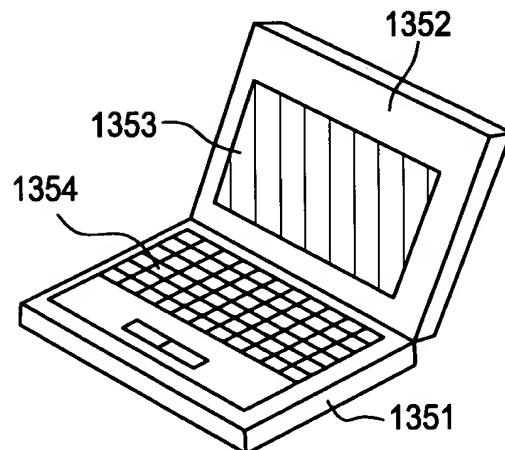


FIG. 13F



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FIG. 14A

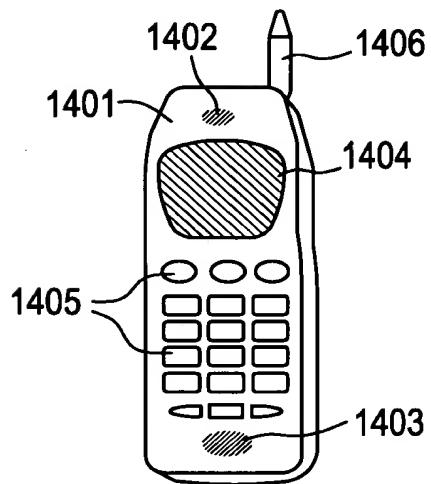


FIG. 14B

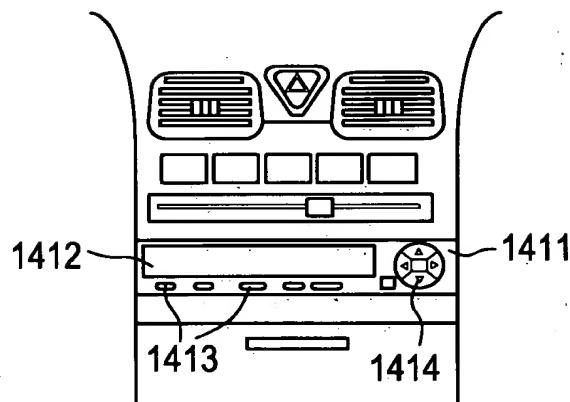


FIG. 14C

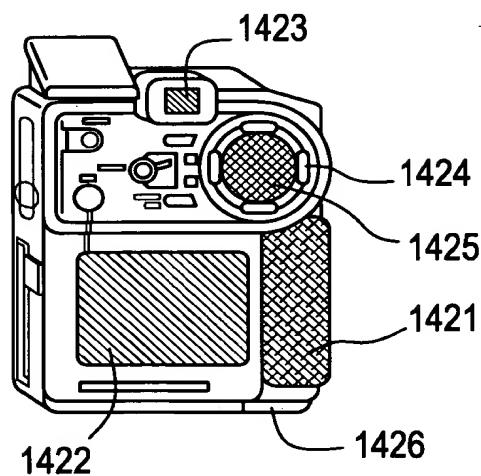
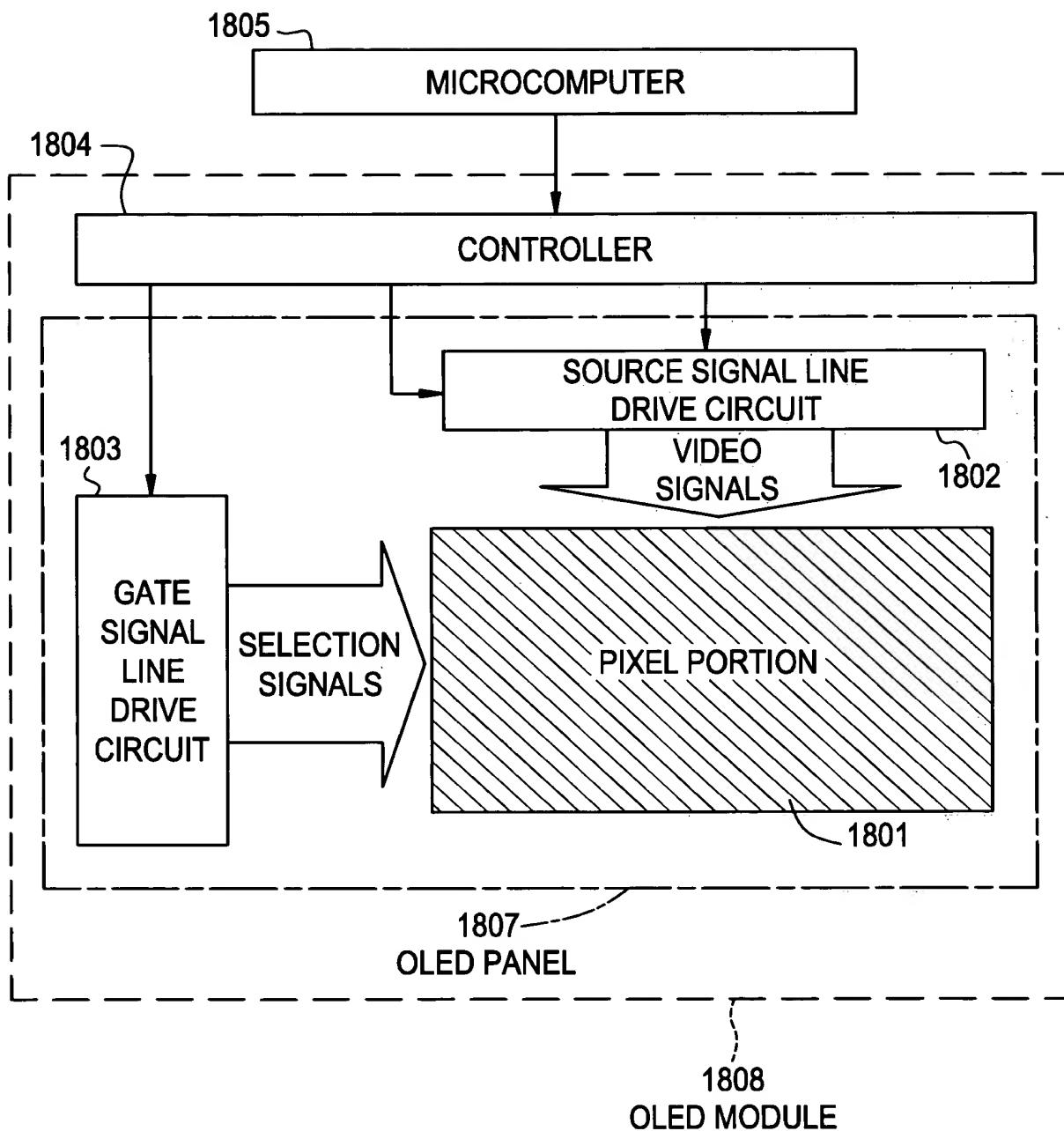




FIG. 15



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FIG. 16A

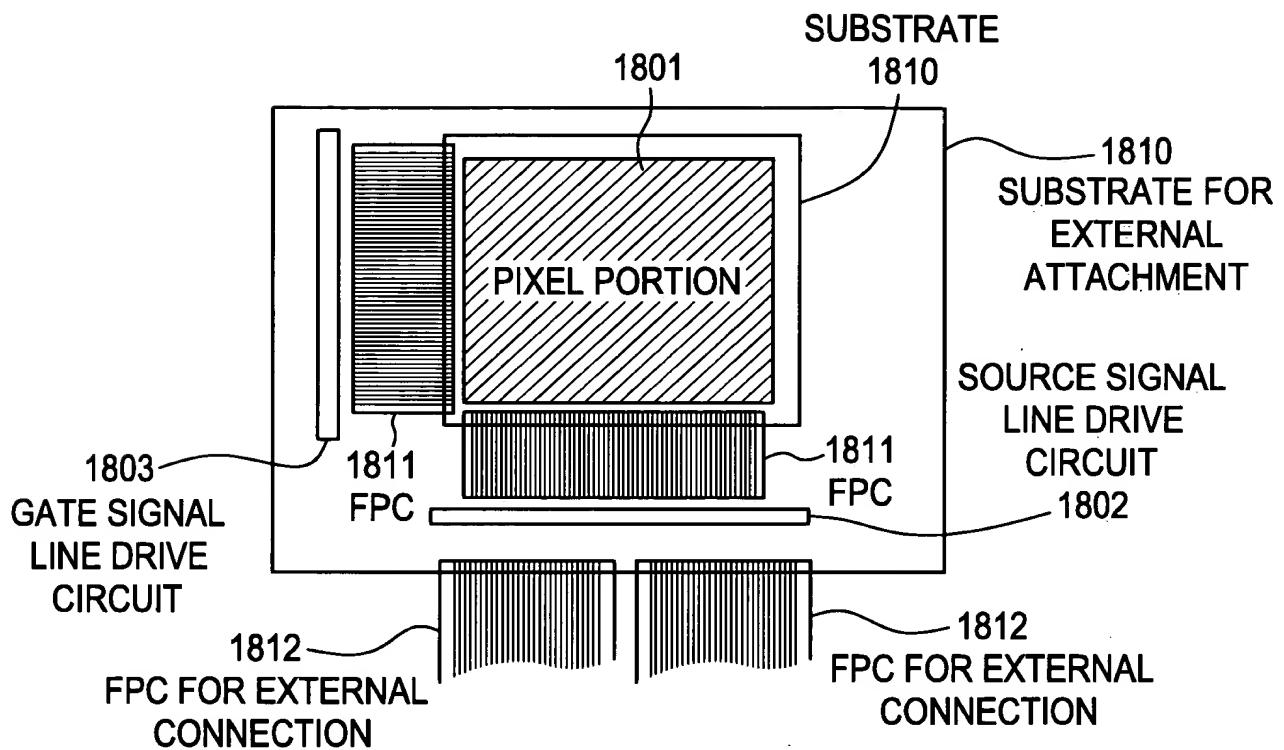


FIG. 16B

